

## EFEK TEMPERATUR *ANNEALING* TERHADAP KINERJA DIODA SCHOTTKY AU/4H-SiC

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### INTISARI

Semikonduktor pita-lebar seperti 4H-SiC banyak diteliti untuk aplikasi di lingkungan ekstrem karena keunggulannya dalam konduktivitas termal, medan *breakdown* tinggi, dan stabilitas suhu. Dioda Schottky berbasis Au/4H-SiC menjadi kandidat kuat untuk detektor karena mampu menghasilkan tinggi penghalang Schottky besar dan arus bocor rendah. Namun, kualitas antarmuka logam-semikonduktor sangat dipengaruhi oleh tahap *annealing* dalam proses fabrikasi, yang belum banyak dievaluasi secara sistematis untuk struktur Au/4H-SiC.

Penelitian ini bertujuan mengkaji pengaruh temperatur *annealing* terhadap karakteristik elektrik dioda Schottky Au/4H-SiC. Proses fabrikasi mencakup pembersihan substrat, deposisi kontak ohmik (Ag) dan Schottky (Au), serta *annealing* pada suhu 300–700 °C. Pengukuran I-V dilakukan menggunakan Keithley 4200A-SCS, dan parameter tinggi penghalang Schottky ( $\phi_B$ ), faktor idealitas (n), serta resistansi seri ( $R_S$ ) diekstraksi menggunakan metode Cheung.

Karakteristik terbaik dicapai pada *annealing* 700 °C dengan nilai  $\phi_B$  sebesar 1,74 eV dan faktor idealitas menurun dari 5,37 menjadi 1,94. Resistansi seri mengalami kenaikan pada suhu 500–600°C, kemungkinan diakibatkan karena pembentukan fase resistif, dan menurun pada suhu 700°C. Kondisi 700°C diidentifikasi sebagai parameter termal optimal untuk menghasilkan dioda Au/4H-SiC dengan performa elektrik unggul, khususnya untuk aplikasi detektor pada suhu tinggi atau lingkungan ekstrem.

**Kata kunci:** 4H-SiC, Dioda Schottky, *Annealing*, Kontak Schottky Au, Karakterisasi Elektrik

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## EFFECT OF ANNEALING TEMPERATURE ON THE PERFORMANCE OF AU/4H-SiC SCHOTTKY DIODES

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### ABSTRACT

Wide-bandgap semiconductors such as 4H-SiC have been extensively studied for applications in extreme environments due to their superior thermal conductivity, high breakdown field, and temperature stability. Schottky diodes based on Au/4H-SiC are considered strong candidates for detector applications, as they offer a high Schottky barrier height and low leakage current. However, the quality of the metal-semiconductor interface is highly influenced by the *annealing* stage in the fabrication process, which has not been systematically evaluated for Au/4H-SiC structures.

This study aims to investigate the effect of *annealing* temperature on the electrical characteristics of Au/4H-SiC Schottky diodes. The fabrication process includes substrate cleaning, deposition of ohmic (Ag) and Schottky (Au) contacts, followed by *annealing* at temperatures ranging from 300 to 700 °C. Current-voltage (I-V) measurements were performed using a Keithley 4200A-SCS, and the parameters Schottky barrier height ( $\phi_B$ ), ideality factor (n), and series resistance ( $R_S$ ) were extracted using the Cheung method.

The optimal performance was achieved at an *annealing* temperature of 700 °C, yielding a Schottky barrier height of 1.74 eV and a significant reduction in the ideality factor from 5.37 to 1.94. The series resistance increased at 500–600 °C, likely due to the formation of a resistive phase, and then dropped significantly at 700 °C. The 700 °C *annealing* condition was identified as the optimal thermal parameter for achieving high-performance Au/4H-SiC diode, particularly for detector applications in high-temperature or harsh environments.

**Keywords:** 4H-SiC, Schottky Diode, *Annealing*, Au Schottky Contact, Electrical Characterization

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